Docket No. 248397US99DIV

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

NEAPPLICATION OF:

Jamai RAMDANI, et al.

NO: 10

10/768,108

GAU:

2815

February 2, 2004

EXAMINER: BAUMEISTER

SEMICONDUCTOR STRUCTURE. SEMICONDUCTOR DEVICE, COMMUNICATING DEVICE,

INTEGRATED CIRCUIT, AND PROCESS FOR FABRICATING THE SAME

## INFORMATION DISCLOSURE STATEMENT UNDER 37 CFR 1.97

COMMISSIONER FOR PATENTS ALEXANDRIA, VIRGINIA 22313

SIR

Applicant(s) wish to disclose the following information.

### REFERENCES

- The applicant(s) wish to make of record the references listed on the attached form PTO-1449. Copies of the listed references are attached, and copies were submitted in Application Serial No. 09/808,888 according to the attached copy of a Granted Petition. This application contains related subject matter.
- A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

#### **RELATED CASES**

- Attached is a list of applicant's pending application(s), published application(s) or issued patent(s) which may be related to the present application. In accordance with the waiver of 37 CFR 1.98 dated September 21, 2004, copies of the cited pending applications are not provided. Cited published and/or issued patents, if any, are listed on the attached PTO form 1449.
- ☐ A check or credit card payment form is attached in the amount required under 37 CFR §1.17(p).

### CERTIFICATION

- ☐ Each item of information contained in this information disclosure statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this statement.
- □ No item of information contained in this information disclosure statement was cited in a communication from a foreign patent office in a counterpart foreign application or, to the knowledge of the undersigned, having made reasonable inquiry, was known to any individual designated in 37 CFR §1.56(c) more than three months prior to the filing of this statement.

# DEPOSIT ACCOUNT

Please charge any additional fees for the papers being filed herewith and for which no check or credit card payment is enclosed herewith, or credit any overpayment to deposit account number <u>15-0030</u>. A duplicate copy of this sheet is enclosed.

Respectfully submitted,

OBLON, SPIVAK, McCLELLAND MAIER & NEUSZADZ, P.C.

Richard L. Treanor

Registration No. 36,379

**Customer Number** 

22850

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Form PTO 1449 (Modified)	U.S. DEPARTMENT OF COMM PATENT AND TRADEMARK OFF	MERCE ICE	ATTY DOCKET NO. 248397US99DIV		SERIAL N	O. 10/768,108	
UST OF RE	PEFERENCES CITED BY API	PLICANT	APPLICANT Jamal F	RAMDANI	et al.		
			FILING DATE		GROUP		
OCT 2	5 2004 (2)		February 2, 2004		2815		
ATTE	<u>\$</u>		U.S. PATENT DOCUMENTS	1.0.400			
EXAMPLE ADE	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS	FILING DATE IF APPROPRIATE	
A-4	3,802,967	04/09/74	Ladany et al.				
AE	3 4,174,422	11/13/79	Matthews et al.		<u> </u>		
AC	4,404,265	09/13/83	Manasevit				
AC	4,482,906	11/13/84	Hovel et al.				
AE	4,523,211	06/11/85	Morimoto et al.				
AF	4,661,176	04/28/87	Manasevit				
AC	G 4,793,872	12/27/88	Meunier et al.				
AF	1 4,846,926	07/11/89	Kay et al.				
A)		08/08/89	Akasaki et al.				
AI		01/02/90	Shastry				
Ar	4,912,087	03/27/90	Aslam et al.				
AL	4,928,154	05/22/90	Umeno et al.				
AN		10/16/90	Wanlass et al.				
AA AA	5,141,894	08/25/92	Bisaro et al.		1		
AC	5,159,413	10/27/92	Calviello et al.				
AF	5,173,474	12/22/92	Connell et al.				
AC	5,221,367	06/22/93	Chisholm et al.				
AF	R 5,225,031	07/06/93	McKee et al.			•	
AS	5,358,925	10/25/94	Neville Connell et al.				
AT	5,393,352	02/28/95	Summerfelt				
AL	J 5,418,216	05/23/95	Fork				
A	/ 5,450,812	09/19/95	McKee et al.		·		
AV	N 5,478,653	12/26/95	Guenzer		<u> </u>		
A	5,482,003	01/09/96	McKee et al.				
A	7 5,514,484	05/07/96	Nashimoto				
AZ		09/17/96	Guenzer				
BA		12/31/96	Sheldon				
BE	1	09/23/97	Schetzina				
ВС	5,733,641	03/31/98	Fork et al.				
ВС		04/07/98	Manti et al.				
ВЕ		04/21/98	Ramdani et al.				
BF		09/22/98	Yano et al.	<u></u>			
ВС		11/03/98	McKee et al.				
В		06/15/99	Jia				
ВІ		02/01/00	Wollesen		ļ <u>.</u>		
B,		04/04/00	Yano et al.		<u> </u>		
B		05/16/00	Northrup et al.	<u> </u>	ļ		
BL	6,064,092	05/16/00	Park		<u>                                     </u>		
81	M 6,096,584	08/01/00	Ellis-Monaghan et al.			· · · · · · · · · · · · · · · · · · ·	
BI	N 6,103,008	08/15/00	McKee et al.			,	
ВС	L`	10/24/00	So				
ВГ	6,174,755	01/16/01	Manning				
В	Q 6,180,486	01/30/01	Leobandung et al.				

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Form PTO 1449 (Modified)	F	U.S. DEPARTMENT OF COMP PATENT AND TRADEMARK OFF	MERCE ICE	ATTY DOCKET NO. 248397US99DIV		SERIAL I	NO. 10/768,108
LIST OF	REFE	RENCES CITED BY API	PLICANT	APPLICANT Jamal F	RAMDANI	et al.	
				FILING DATE		GROUP	
		· · · · · · · · · · · · · · · · · · ·		February 2, 2004		L	2815
EXAMINER		DOCUMENT	DATE	U.S. PATENT DOCUMENTS NAME	CLASS	SUB	FILING DATE
INITIAL		NUMBER			CLASS	CLASS	IF APPROPRIATE
	CA	3,766,370	10/16/73	Walther			
	СВ	4,006,989	02/08/77	Andringa			
	CC	4,284,329	08/18/81	Smith et al.			
	CD	4,777,613	10/11/98	Shahan et al.			
	CE	4,802,182	01/31/89	Thornton et al.			
	CF	4,882,300	11/21/89	Inoue et al.			
	CG	4,896,194	01/23/90	Suzuki			
	СН	4,999,842	03/12/91	Huang et al.			
	CI	5,081,062	01/14/92	Vasudev et al.			
	CI	5,155,658	10/13/92	inam et al.		,	
	СК	5,248,564	09/28/93	Ramesh			
	CL	5,260,394	11/09/93	Tazaki et al.	_	<b></b>	-
	СМ	5,270,298	12/14/93	Ramesh	ļ	ļ	
	CN	5,286,985	02/15/94	Taddiken		ļ	
	co	5,310,707	05/10/94	Oishi et al.			<u>.</u>
	СР	5,326,721	07/05/94	Summerfelt	-		
	CQ	5,404,581	04/04/95	Honjo		ļ	
	CR	5,418,389	05/23/95	Watanabe			
	cs	5,436,759	07/25/95	Dijail et al.		ļ	
	СТ	5,576,879	11/19/96	Nashimoto	_	<u> </u>	
	CU	5,606,184	02/25/97	Abrokwah, et al.	<u> </u>		
	CV	5,640,267	06/17/97 10/07/97	May et al. Hayashi et al.	<u> </u>	-	
	CW CV	5,674,366 5,729,641	03/17/98	Chandonnet et al.			
	СХ			Ho	-		
	CY	5,790,583	08/04/98	<u></u>		<del>  </del>	
·	DA	5,825,799 5,857,049	10/20/98 01/05/99	Ho et al. Beranek et al.	-		
	DB DB	. L	02/23/99	Brunel et al.		<del>  </del>	
		5,874,860 5,926,496	07/20/99	Ho et al.	<del></del>		
	DC DD	5,937,285	08/10/99	Abrokwah, et al.			<del></del>
	DE	5,981,400	11/09/99	Lo	+		
	DF	5,990,495	11/23/99	Ohba	<del> </del>		
	DG	6,002,375	12/14/99	Corman et al.	<del> </del>		
	DH	6,008,762	12/28/99	Nghlem	<del> </del>		
	DI.	6,055,179	04/25/00	Koganel et al.	-		
	DJ DJ	6,107,653	08/22/00	Fitzgerald	+		
	DK	6,113,690	09/05/00	Yu et al.	+	-	
<b></b>	DL DL	6,114,996	09/05/00	Nghiem	+		
	DM DM	6,121,642	09/19/00	Newns		<b>}</b>	
	DN	6,128,178	10/03/00	Newns	<del> </del>	<del>  </del>	
	00	6,143,072	11/07/00	McKee et al.	+		****
	DP	6,184,144	02/06/01	Lo	+	<del> </del>	
	DQ DQ	6,222,654	04/24/01	Frigo	<del>                                     </del>	<del>  </del>	
<u> </u>				1		<u>1</u>	

							HEET 3 OF 2	
Form PTO 1449 (Modified)	P	U.S. DEPARTMENT OF C PATENT AND TRADEMARK		ATTY DOCKET NO. 248397US99DIV		SERIAL	NO. 10/768,108	
LIST OF	REFE	RENCES CITED BY	APPLICANT	APPLICANT  Jamal RAMDANI, et al.				
			•	FILING DATE		GROUP	0045	
				February 2, 2004			2815	
EXAMINER	Γ.	DOCUMENT		U.S. PATENT DOCUMENTS NAME	CLASS	SUB	FILING DATE	
NITIAL	EA	NUMBER 4,484,332	11/20/84	Hawrylo	<del></del>	CLASS	IF APPROPRIATE	
	EB	4,815,084		Scifres et al.		<del> </del>		
	EC	4,876,219		Eshita et al.	<del></del>	<del>                                      </del>		
	ED	4,963,508		Umeno et al.		+		
-	EE	5,060,031		Abrokwah, et al.	<del> </del>	-		
	EF	5,063,166		Mooney et al.	-	-		
	EG EG	5,116,461		Lebby et al.				
	EH	5,127,067	06/30/92	Delcoco et al.	_			
	EI	5,144,409		Ma	+	<del> </del>	<del> </del> -	
-	EJ.	5,293,050	1	Chappie-Sokol et al	<del> </del>	+	<del>                                     </del>	
	EK	5,356,831	10/18/94	Calviello et al.		<del> </del>		
	EL	5,391,515		Kao et al.		<del> </del>		
·	EM	5,442,191	08/15/95	Ma	-	1		
	EN	5,444,016	08/22/95	Abrokwah, et al.	+	<del> </del>		
	EO	5,480,829		Abrokwah, et al.	<del></del>	+		
	EP	5,528,414	06/18/96	Oakley		+	<del> </del>	
	EQ.	5,614,739	03/25/97	Abrokwah et al.	<del> </del>	†	-	
	ER	5,729,394	03/17/98	Sevier et al.	+	†		
	ES	5,731,220	03/24/98	Tsu et al.			-	
	ET	5,764,676	06/09/98	Paoli et al.	1			
•	EU	5,777,762	07/07/98	Yamamoto		<del> </del>		
	EV	5,778,018	07/07/98	Yoshikawa et al.		<del> </del>		
	EW	5,778,116	07/07/98	Tomich	<del> </del>			
	EX	5,801,105	09/01/98	Yano et al.	<del> </del>	<del>                                     </del>		
	EY	5,828,080	10/27/98	Yano et al.				
	EZ	5,858,814	01/12/99	Goossen et al.	<del> </del>	<del> </del>		
	FA	5,861,966	01/19/99	Ortel	+	1		
	FB	5,883,996	03/16/99	Knapp et al.		<del>                                     </del>		
	FC	5,995,359	11/30/99	Klee et al.				
<u></u>	FD	6,058,131	05/02/00	Pan	1			
	FE	6,137,603	10/24/00	Henmi		1		
	FF	6,146,906	11/14/00	Inoue et al.	1	1	<del>                                     </del>	
	FG	6,173,474	01/16/01	Conrad	<del>                                     </del>			
	FH	6,180,252	01/30/01	Farrell et al.	1	1		
	FI	4,242,595	12/30/0	Lehovec	1	<del> </del>		
	FJ	4,398,342	08/16/83	Pitt et al.	1		<u> </u>	
	FK	4,424,589	01/03/84	Thomas et al.	1	<u> </u>		
	FL	4,876,208	10/24/89	Gustafson et al.	-	<del> </del>		
	FM	4,482,422	11/84	McGinn et al.				
	FN	4,667,088	05/19/87	Kramer	1	1 -		
	FO	4,772,929	09/20/88	Manchester et al.	<del> </del>	1		
-	FP	4,841,775	06/27/89	lkeda et al.	1	1		
	FQ	4,845,044	07/04/89	Ariyoshi et al.	<del>                                     </del>	1		

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orm PTO 1449 Modified)				ATTY DOCKET NO. 248397US99DIV		SERIAL N	10. 10/768,108
LIST OF REFERENCES CITED BY APPLICANT		APPLICANT  Jamal RAMDANI, et al.					
2.01 0.			FILING DATE		GROUP		
		···		February 2, 2004			2815
				U.S. PATENT DOCUMENTS NAME	CLASS	SUB	FILING DATE
EXAMINER INITIAL		DOCUMENT NUMBER	DATE		CLASS	CLASS	IF APPROPRIATE
	GA	4,868,376	09/19/89	Lessin et al.			
	GB	4,885,376	12/05/89	Verkade			
	GC	4,888,202	12/89	Murakami et al.			
	GD	4,891,091	12/90	Wanlass et al.			
	GE	5,051,790	09/24/91	Hammer			
	GF	5,055,445	10/08/91	Belt et al.			
	GG	5,081,519	11/14/92	Nishimura et al.			
	GH	5,143,854	09/01/92	Pirrung et al.			
	GI	5,185,589	02/09/93	Krishnaswamy et al.			
	GJ	5,191,625	03/02/93	Gustavsson			
	GK	5,194,397	03/16/93	Cook et al.			
	GL	5,208,182	05/04/93	Narayan et al.			
	GM	5,216,729	06/01/93	Berger et al.			
	GN	5,314,547	05/24/94	Heremans et al.			
	GO	5,352,926	10/04/94	Andrews			
	GP	5,356,509	10/18/94	Terranova et al.			
	GQ	5,371,734	12/06/94	Fischer			
	GR	5,372,992	12/94 .	Itozaki et al.			
	GS	5,405,802	04/11/95	Yamagata et al.			
	GT	5,442,561	08/15/95	Yoshizawa et al.			
	GU	5,453,727	09/26/95	Shibasaki et al.			
	GV	5,466,631	11/14/95	Ichikawa et al.			
	GW	5,473,047	12/05/95	Shi		İ	
	GX	5,473,171	12/95	Summerfelt			
·	GY	5,479,033	12/26/95	Baca et al.			
	GZ	5,486,406	01/23/96	Shi		1	
	HA	5,491,461	02/13/96	Partin et al.			·
	нв	5,492,859	02/20/96	Sakaguchi et al.			
	нс	5,494,711	02/27/96	Takeda et al.			
	HD	5,504,035	04/02/96	Rostoker et al.			-
	HE	5,504,183	04/02/96	Shi			
	HF	5,511,238	04/23/96	Bayraktaroglu	<del>                                     </del>		
	HG	5,512,773	04/96	Wolf et al.	1		
	нн	5,515,047	05/07/96	Yamakido et al.		1	
	н	5,515,810	05/14/96	Yamashita et al.			·
	HJ	5,519,235	05/96	Ramesh			<del> </del>
	HK	5,549,977	08/96	Jin et al.	<del> </del>		
<del></del> -	HL	5,551,238	09/03/96	Prueitt	<b></b>		
	НМ	5,552,547	09/03/96	Shi			
	HÑ	5,589,284	12/31/96	Summerfelt et al.			
	но	5,602,418	02/11/97	lmai et al.	ļ	<del> </del>	
	HP	5,633,724	05/27/97	King et al.	<del> </del>	<del>                                     </del>	

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Form PTO 1449 (Modified)	1	U.S. DEPARTMENT OF COM PATENT AND TRADEMARK OFF	MERCE	ATTY DOCKET NO. 248397US99DIV		SERIAL I	NO. 10/768,10	08
LIST OF	REFE	ERENCES CITED BY AP	PLICANT	APPLICANT Jamai RA	MDANI.	et al.		
				FILING DATE		GROUP		
				February 2, 2004		· .	2815	
			-	U.S. PATENT DOCUMENTS		T 6115		
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS		OPRIATE
	IA	5,650,646	07/22/97	Summerfelt				
	IB	5,656,382	08/12/97	Nashimoto				
	C	5,659,180	08/19/97	Shen et al.	-			
	ID	5,661,112	08/26/97	Hatta et al.				
	IE.	5,679,965	11/95	Schetzina	_			
	JF.	5,725,641	03/10/98	MacLeod				
	IG	5,745,631	04/28/98	Reinker				
	Н	5,776,621	07/07/98	Nashimoto				
	11	5,777,350	07/07/98	Nakamura et al.				
	IJ	5,789,845	08/04/98	Wadaka et al.				<del>-</del>
	IK	5,792,569	08/11/98	Sun et al.				
	L	5,792,679	08/11/98	Nakato				
	М	5,796,648	08/18/98	Kawakubo et al.				
	N	5,801,072	09/01/98	Barber				
	0	5,812,272	09/22/98	King et al.				
	£	5,814,583	09/98	itozaki et al.				
	Q	5,825,055	10/20/98	Summerfelt				
	IR	5,827,755	10/27/98	Yonchara et al.				
	IS	5,833,603	11/10/98	Kovacs et al.				
	ìΤ	5,838,035	11/17/98	Ramesh				
	U	5,844,260	12/01/98	Ohori				
	IV	5,846,846	12/08/98	Suh et al.				
	IW	5,863,326	01/26/99	Nause et al.				
	iX	5,872,493	02/16/99	Ella				
	IΥ	5,879,956	03/99	Seon et al.				
	ız	5,880,452	03/09/99	Plesko				•
	JA	5,883,564	03/16/99	Partin .				
	JB	5,907,792	05/25/99	Droopad et al.				
	JC	5,937,274	08/10/99	Kondow et al.			<u> </u>	
	סנ	5,948,161	09/07/99	Kizuki		i		
	ĴΕ	5,959,879	09/28/99	Коо		<del></del>		
	JF	5,966,323	10/99	Chen et al.		<del></del>		
	JG	5,987,011	11/16/99	Toh				
	JH	6,022,140	02/08/00	Fraden et al.				
	JI	6,022,410	02/08/00	Yu et al.				
	IJ	6,023,082	02/08/00	McKee et al.	_		•	
	JK	6,028,853	02/22/00	Haartsen				
	JL	6,049,702	04/11/00	Tham et al.		1		
	JM	6,078,717	06/20/00	Nashimoto et al	***		·	···
	JN	6,088,216	07/00	Laibowitz et al.			<del></del>	
	10	6,090,659	07/00	Laibowitz et al.				
	JP	6,107,721	08/22/00	Lakin				<u> </u>
	JQ	6,153,010	11/28/00	Kiyoku et al				

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Form PTO 1449 (Modified)	P	U.S. DEPARTMENT OF COMP ATENT AND TRADEMARK OFF		ATTY DOCKET NO.  248397US99DIV		SERIAL	iO. 10/768,108	
LIST OF	LIST OF REFERENCES CITED BY APPLICANT			APPLICANT  Jamal RAMDANI, et al.				
				FILING DATE		GROUP		
				February 2, 2004	<del></del>	<u> </u>	2815	
EVALUMED		DOCUMENT	DATE	U.S. PATENT DOCUMENTS NAME	TCLASS	SUB	FILING DATE	
EXAMINER INITIAL		NUMBER			CEAGG	CLASS	IF APPROPRIATE	
	KA	6,153,454	11/28/00	Krivokapic				
	кв	6,191,011	02/01	Gilboa et al	<u> </u>		···	
	KC	6,204,737	03/20/01	Ella				
	KD	6,224,669	05/01/01	Yi et al.				
	KE	6,225,051	05/01/01	Sugiyama et al.				
	KF	6,241,821	06/05/01	Yu et al.	<u> </u>	- 1		
	KG	6,265,749	07/24/01	Gardner et al.	<u> </u>			
	кн	6,313,486	11/01	Kencke et al.				
	KI	6,316,832	11/13/01	Tsuzuki et al.	1			
	KJ	2002/0008234	01/02	Emrick				
_	KK	3,670,213	06/13/72	Nakawaga et al.				
	KL	4,756,007	07/05/88	Qureshi et al.				
	KM	4,773,063	09/20/88	Hunsperger et al.				
	KN	5,394,489	02/28/95	Koch				
	ко	5,406,202	04/11/95	Mehrgardt et al.				
	KP	5,528,067	06/18/96	Farb et al.				
_	KQ	5,572,052	11/05/96	Kashihara et al.				
	KR	5,767,543	06/16/98	Oorns et al.	<u> </u>			
	KS	6,175,497	01/16/01	Tseng et al.				
	кт	6,197,503	03/06/01	Vo-Dinh et al.	<u> </u>			
	ΚU	6,248,459	06/19/01	Wang et al.			<del>, , ,</del>	
	KV	6,252,261	06/26/01	Usui et al.				
	ĸw	6,255,198	07/03/01	Linthicum et al.	ļ		<del></del>	
	кх	6,268,269	07/31/01	Lee et al.				
	KY	6,291,319	09/18/01	Yu et al.				
	ΚZ	6,316,785	11/13/01	Nunoue et al.				
	LA	6,343,171	01/29/02	Yoshimura et al.			·	
	LB	4,965,649	10/23/90	Zanio et al.		ļ		
	LC	6,253,649	05/01	Kawahara et al.		<b> </b>		
	LD	6,211,096	04/01	Aliman et al.	<del> </del>			
	LE	6,239,449	05/29/01	Fafard et al.	<del>                                     </del>			
	LF	2001/0013313	08/16/01 02/06/01	Droopad et al. Sone et al.	<del> </del>	<del>                                     </del>		
	LG	6,184,044	02/06/01	Mirkarimi et al.		<del> </del>		
	LH	6,011,646 5,227,196	07/13/93	Itoh	+			
	LI	6,150,239	11/21/00	Goesele et al.	<del> </del>	<del>                                     </del>		
	LK	5,441,577	08/15/95	Sasaki et al.	<del> </del>	<del>                                     </del>	<del></del>	
	LL	4,459,325	07/10/84	Nozawa et al.	<del> </del>	<del>  </del>	··	
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	LM	4,392,297 4,289,920			<del>                                     </del>			
	LM LN	4,289,920	09/15/81	Hovel				
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· LIST OF REFERENCES CITED BY APPLICANT		APPLICANT Jamai R	et al.				
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	MA	5,553,089	09/03/96	Seki et al.			
	MB	5,528,057	06/18/96	Yanagase et al.			
	MC	6,229,159	05/08/01	Suzuki			
	MD	4,748,485	05/31/88	Vasudev			·
•	ME	4,984,043	01/08/91	Vinal			
	MF	5,754,319	05/19/98	Van De Voorde et al.			
	MG	6,108,125	08/22/00	Yano			·
	мн	5,073,981	12/17/91	Giles et al.			
	МІ	5,140,651	08/18/92	Soref et al.			
	MJ	5,610,744	03/11/97	Ho et al.			-
	MK	6,362,017	03/26/02	Manabe et al.			
	ML	6,242,686	06/05/01	Kishimoto et al.			
	ММ	5,689,123	11/18/97	Major et al.	***************************************		
	MN	5,670,800	09/23/97	Nakao et al.			
	МО	5,067,809	11/26/91	Tsubota			
	MP	5,596,205	01/21/97	Reedy et al.			
	MQ	6,175,555	01/16/01	Hoole			
	MR	5 ,357,122	10/18/94	Okubora et al.			
	MS	4,084,130	04/11/78	Holton			******
	мт	6,093,302	07/25/00	Montgomery			
	MU	6,372,813	04/16/02	Johnson et al.			
	MV	5,608,046	03/04/97	Cook et al.			
	MW	5,955,591	09/21/99	Imbach et al.	,		
	МХ	6,022,963	02/08/00	McGall et al.			
-	MY	6,083,697	07/04/00	Beecher et al.			
	MZ	5,063,081	11/05/91	Cozzette et al.			
	NA	5,479,317	12/26/95	Ramesh			
	NB	5,306,649	04/26/94	Hebert	<del></del>		
	NC	5,962,069	10/05/99	Schindler et al.			- · · · · · · · · · · · · · · · · · · ·
	ND	5,541,422	07/30/96	Wolf et al.			
	NE	5,873,977	02/23/99	Desu et al.			
	NF	5,538,941	07/23/96	Findikoglu et al.			
	NG	6,046,464	04/04/00	Schetzina			
	NH	6,235,145	05/22/01	Li et al.			
	NI	5,610,744	03/11/97	Ho et al.			-
	NJ	5,280,013	01/18/94	Newman et al.	·		
	NK	6,348,373 B1	02/19/02	Ma et al.			
	NL	6,339,664 B1	01/15/02	Farjady et al.		( - 1	•
	NM	4,439,014	03/27/84	Stacy et al.			
	NN	4,889,402	12/26/89	Reinhart			
	NO	5,963,291	10/05/99	Wu et al.			
	NP	6,011,641	01/04/00	Shin et al.	-		
	NQ	6,340,788 B1	01/22/02	King et al.			

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	OA	5,807,440	09/15/98	Kubota et al.				
	ОВ	4,681,982	07/21/87	Yoshida				
	ОС	4,629,821	12/16/86	Bronstein-Bonte et al.				
	OD	4,452,720	06/05/84	Harada et al.				
	OE	3,935,031	01/27/76	Adler				
	OF	5,760,426	06/02/98	Marx et al.				
	OG	5,053,835	10/01/91	Horikawa et al.				
	ОН	6,326,645.B1	12/04/01	Kadota				
	OI	5,770,887	06/23/98	Tadatomo et al.				
	OJ	6,372,356 B1	04/16/02	Thornton et al.				
	ОК	4,774,205	09/27/88	Choi et al.				
	OL	6,359,330 B1	03/19/02	Goudard				
	ОМ	5,312,765	05/17/94	Kanber				
	ON	5,734,672	03/31/98	McMinn et al.				
	00	6,367,699 B2	04/09/02	Ackley				
	OP	5,530,235	06/25/96	Stefik et al.				
	OQ.	5,623,552	04/22/97	Lane				
	OR	5,481,102	01/02/96	Hazelrigg, Jr.				
	os	6,134,114	10/17/00	Ungermann et al.				
	ОТ	5,984,190	11/16/99	Nevill				
	OU	5,789,733	08/04/98	Jachlmowicz et al.				
	٥٧	5,753,300	05/19/98	Wessels et al.				
	ow	6,208,453	03/27/01	Wessels et al.				
	ОХ	5,886,867	03/23/99	Chivukula et al.				-
	OY	5,028,976	07/02/91	Ozaki et al.				
	OZ	5,869,845	02/09/99	Vander Wagt et al.				
	PA	5,596,214	01/21/97	Endo				
	РВ	6,391,674 B2	05/21/02	Ziegler				
	PC	6,275,122 B1	08/14/01	Speidell et al.				
	PD	6,238,946 B1	05/29/01	Ziegler				
	PE	6,210,988 B1	04/03/01	Howe et al.				
	PF	6,392,257	05/21/02	Ramdani et al.				
	PG	4,442,590	04/17/84	Stockton et al.				
	PH	5,603,764	02/18/97	Matsuda et al.				
	PI	6,087,681	06/11/00	Shakuda				· · · · · · · · · · · · · · · · · · ·
	PJ	5,132,648	07/21/92	Trinh et al.				
	PK	6,427,066	07/30/02	Grube				
	PL	2002/0072245	06/13/02	Ooms et al.		· · · ·		
	РМ	6,278,138 B1	08/21/01	Suzuki				
	PN	5,888,296	03/30/99	Ooms et al.				
	PO	5,198,269	03/3093	Swartz et al.				
	PP	2002/0030246	03/14/02	Eisenbeiser et al.				
	PQ	2002/0047143	04/25/02	Ramdani et al.				

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	QA	5,776,359	07/07/98	Schultz et al.	,			
	QB	5,569,953	10/29/96	Kikkawa et al.				
	QC	5,834,362	11/10/98	Miyagaki et al.	ļ			
	QD	6,248,621 81	06/19/01	Wilk et al.				
	QE	5,266,355	11/30/93	Wemberg et al.				
	QF	6,277,436 B1	08/21/01	Stauf et al.				
	QG	6,039,803	03/21/00	Fitzgerald et al.	<u> </u>			
	ă	5,619,051	04/08/97	Endo				
	QI	5,420,102	05/30/95	Harshavardhan et al.				
	σı	5,210,763	05/11/93	Lewis et al.				
	QK	5,103,494	04/07/92	Mozer				
	QL	4,594,000	06/10/86	Falk et al.				
	QM	4,297,656	10/27/81	Pan				
	QN	5,244,818	09/14/93	Jokers et al.				
	QO	6,048,751	04/11/00	D'Asaro et al.	1			
	QP	5,484,664	01/16/96	Kitahara et al.	1	1		
	QQ	5,780,311	07/14/98	Beasom et al.				
	QR	6,438,281 B1	08/20/02	Tsukamoto et al.				
	QS	5,399,898	03/21/95	Rostoker				
•	QT	6,271,619	08/07/01	Yamada et al.			-	
	QU	5,334,556	08/02/94	Guldi				
	QV	4,910,164	03/20/90	Shichijo	i			
	QW	4,952,420	08/28/90	Walters	1			
	QΧ	6,121,647	09/19/00	Yano et al.	1			
	QY	6,306,668 B1	10/23/01	McKee et al.	<del></del>			
	QZ	6,143,366	11/07/00	Lu	<del>                                     </del>			
	RA	6,410,941	06/25/02	Taylor et al.	<del> </del>			
	RB	5,397,428	03/14/95	Stoner et al.				
	RC	6,432,546 B1	08/13/02	Ramesh et al.	1			
	RD	6,345,424	02/12/02	Hasegawa et al.	<b></b>	<del>  </del>	<del></del>	
···········	RE	6,338,756 B2	01/15/02	Dietze	<u> </u>	<del>                                     </del>		
	RF	5,516,725	05/14/96	Chang et al.				
	RG	4,667,212	05/19/87	Nakamura	†			
	RH	5,629,534	05/13/97	Inuzuka et al.	1			
	RI	3,914,137	10/21/75	Huffman et al.	1	<del>                                     </del>		
	RJ.	5,753,928	05/19/98	Krause	1	<del>                                     </del>		
	RK	5,977,567	11/02/99	Verdiell	<del> </del>	<del>                                     </del>		
	RL	5,130,762	07/14/92	Kulick	<del> </del>	<del>  .  </del>		
	RM	5,621,227	04/15/97	Joshi	+	<del>                                     </del>		
	RN	6,389,209 B1	05/14/02	Suhir	<del>  -</del>	<del>                                     </del>		
				Lorenzo et al.	<del> </del>	<del>                                     </del>		
	RO	5,163,118	11/10/92		<del> </del>	<del>                                     </del>		
	RP	5,926,493	07/20/99	O'Brien et al.	+	<del>                                     </del>		
,	RQ	5,323,023	06/21/94	Fork		<u> </u>		

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	SA	6,156,581	12/05/00	Vaudo et al.			
	SB	5,395,663	03/07/95	Tabata et al.	<u> </u>		
	SC	4,146,297	03/27/79	Alferness et al.	<u> </u>		
	SD	5,452,118	09/19/95	Maruska			
	SE	5,889,296	03/30/99	Imamura et al.			
	SF	6,300,615 B1	10/09/01	Shinohara et al.			
	SG	6,232,910 B1	05/15/01	Bell et al.			
	SH	5,686,741	11/11/97	Ohori et al.			
	SI	4,959,702	09/25/90	Moyer et al			
	SJ	6,100,578	08/08/00	Suzuki			
	SK	6,410,947 B1	06/25/02	Wada	•		
	SL	6,417,059 B2	07/09/02	Huang			
	SM	6,461,927 B1	10/08/02	Mochizuki et al.			
	SN	6,462,360 B1	10/08/02	Higgins, Jr. et al.			<u> </u>
	so	5,981,976	11/09/99	Murasato			
	SP	5,981,980	11/09/99	Miyajima et al.	1		
	SQ	2002/0006245 A1	01/17/02	Kubota et al.			
	SR	2002/0131675 A1	09/19/02	Litvin			<u> </u>
	SS	6,256,426 B1	07/03/01	Duchet			
	ST	6,278,523 B1	08/21/01	Gorecki			
	su	6,319,730 B1	11/20/01	Ramdani et al.		İ	
	sv	6,404,027	06/11/02	Hong et af.			
	sw	6,312,819 B1	11/06/01	Jia et al.			
	SX	5,119,448	06/02/92	Schaefer et al.			
	SY	4,120,588	10/17/78	Chaum			
	SZ	5,194,917	03/16/93	Regener			
	TA	5,018,816	05/28/91	Murray et al.			
	ТВ	5,953,468	09/14/99	Finnila et al.			
	TC	5,561,305	10/01/96	Smith			
	TD	5,896,476	04/20/99	Wisseman et al.			
	TE	4,934,777	06/19/90	Jou et al.			
	TF	6,320,238 B1	11/20/01	Kizilyalli et al.	1		*
	TG	6,393,167 B1	05/21/02	Davis et al.			
	тн	5,760,427	06/02/98	Onda			· · · · · · · · · · · · · · · · · · ·
	TI	6,411,756 B2	06/25/02	Sadot et al.			
	TJ	5,668,048	09/16/97	Kondo et al.	1		
	TK	5,852,687	12/22/98	Wickham	1		
	TL	5,122,852	06/16/92	Chan et al.			
	ТМ	5,173,835	12/22/92	Comett et al.	1	1	
	TN	5,055,835	10/08/91	Sutton			
	то	6,139,483	10/31/00	Seabaugh et al.			
	TP	5,283,462	02/01/94	Stengel			
	TQ	6,103,403	08/15/00	Grigorian et al.	1		

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	ŲA	5,635,433	06/03/97	Sengupta				
	UB	5,427,988	06/27/95	Sengupta et al.				
	UC	6,297,842 B1	10/02/01	Koizumi et al.				
	UD	5,682,046	10/28/97	Takahashi et al.				
	UE	5,181,085	01/19/93	Moon et al.				
	UF	6,051,858	04/18/00	Uchida et al.				
	UG	6,013,553	01/11/00	Wallace et al.				
	UH	4,872,046	10/03/89	Morkoc et al.				
	UI	2002/0047123 A1	04/25/02	Ramdani et al.				
	UJ	5,995,528	11/30/99	Fukunaga et al.				
	UK	5,075,743	12/24/91	Behfar-Rad				
	UL	5,438,584	08/01/95	Paoli et al.				
	UM	4,503,540	03/05/85	Nakashima et al.				
	UN	5,373,166	12/13/94	Buchan et al.				
	UO	6,278,137 B1	08/21/01	Shimoyama et al.				
	UP	5,623,439	04/22/97	Gotoh et al.				
	UQ	4,981,714	01/01/91	Ohno et al.				
	UR	6,194,753 B1	02/27/01	Seon et al.				
	US	6,326,637 B1	12/04/01	Parkin et al.				
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	AAC	0 455 526	06/11/91	EP	×	
	AAD	0 602 568	06/22/94	EP	×	
	AAE	0 607 435	07/27/94	EP	×	
	AAF	1 001 468	05/17/00	EP	×	
	AAG	0 514 018	11/19/92	EP	×	
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	AAO	52-88354	07/23/77	Japan w/English Abstract	×	
	AAP	54-134554	10/19/79	Japan w/English Abstract	×	
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	AAS	6-232126	08/19/94	Japan	×	
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	AAV	63-131104	06/03/88	Japan w/English Abstract	×	
	AAW	63-198365	08/17/88	Japan w/English Abstract	×	
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	AAY	6-334168	12/02/94	Japan	×	
	AAZ	WO 99/63580	12/09/99	WIPO	×	
	ABA	WO 99/14804	03/25/99	WIPO	×	
	ABB	WO 97/45827	12/04/97	WIPO		
	ABC	WO 99/19546	04/22/99	WIPO		
	ABD	WO 00/33363	06/08/00	WIPO		
	ABE	WO 00/48239	08/17/00	WIPO		
	ABF	WO 99/14797	03/25/99	WIPO		
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	ABH	1 109 212	06/20/01	Europe		
	ABI	DE 197 12 496	10/30/97	Germany		×
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	ABK	60-210018	10/22/85	Japan w/English Abstract		1
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	ABM	0 682 266	11/15/95	Europe	<u> </u>	
	ABN	3-41783	02/91	Japan (English Abstract only)		
	ABO	0 581 239	02/02/94	Europe		
	ABP	0812494	01/16/96	Japan		
	ABQ	2 000 1645	06/16/00	Japan	<del>                                     </del>	

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_	BAC	64-50575	02/27/89	Japan		
	BAD	WO 98/05807	01/12/98	WIPO		
	BAE	WO 94/03908	02/17/94	WIPO		
	BAF	WO 01/33585	05/10/01	WIPO		
	BAG	1-102435	04/20/89	Japan w/English Abstract		<u> </u>
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	BAK	64-52329	02/28/89	Japan (w/English Abstract)		
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KKAH Mitsubishi Semiconductors Press Release (GaAs FET's) November 8, 1999 pp.1-2					
	KKAI	R.J. Matyl et al; "Selected Area Hete Films; 181 (1989) December 10; No.	roepitaxial Growth of GaAs on Silicon for Advance 1; pp. 213-225	ced Device Structures"; 2194 Thin Solid	
	KKAJ	K. Nashimoto et al; "Patterning of Nt Phase Epitaxy"; Applied Physics Let	o, LaOnZr, TiO3 Waveguides for Fabricating Mic ters; Vol. 75, No. 8; 23 August 1999; pp. 1054-10	ro-Optics Using Wet Etching and Solid- 056	
	KKAK	Bang-Hung Tsao et al; "Sputtered Bang-Hung Tsao et al; "Sputtered	arium Titanate and Barium Strontium Titanate Fil Proceedings of the 2000 12th International Sym	ms for Capacitor Applications"; posium on Vol. 2; pp. 837-840	
	KKAL	Man Fai Ng et al; "Heteroepitaxial gr Materials Research; Vol. 12, No. 5; s	owth of lanthanum aluminate films derived from ( pp. 1308	mixed metal nitrates"; Journal of	
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	KKAN	S.A. Chambers et al.; "Epitaxial Grovol. 79, No. 21; November 19, 2001	wth and Properties of Ferromagnetic Co-Doped 1 pp. 3467-3469	TiO2 Anatase*; Applied Physics Letters;	
	KKAO				
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	UT	5,528,209	06/18/96	Macdonald et al.			
	UV	5,998,781	12/07/99	Vawter et al.			
	UW	6,110,813	08/29/00	Ota et al.			
	UX	6,452,232 B1	09/17/02	Adan			
	UY	6,049,110	04/11/00	Koh			
	UZ	5,559,368	09/24/96	Hu et al.			
	VA	6,392,253 B1	05/21/02	Saxena			
	VB	5,585,288	12/17/96	Davis et al.			
	VC	5,268,327	12/07/93	Vernon			
	VD	6,198,119 B1	03/06/01	Nabatame et al.			
	VE	6,113,225	09/05/00	Miyata et al.			
	VF	5,262,659	11/16/93	Grudkowski et al.			
	VG	6,239,012 B1	05/29/01	Kinsman	<b> </b>		
	VH	6,297,598	10/02/01	Wang et al.			
	VI	2002/140012	10/03/02	Droopad			
	٧J	4,866,489	09/12/89	Yokogawa et al.			
	VK	6,080,378	06/27/00	Yokota et al.			
	VL	5,508,554	04/16/96	Takatani et al.			
	VM	6,477,285 B1	11/05/02	Shanley			
	VN	4,695,120	09/22/87	Holder			
	vo	5,882,948	03/16/99	Jewell			
	VP	5,574,589	11/12/96	Feuer et al.			
	VQ	5,510,665	04/23/96	Conley			
	VR	4,804,866	02/14/89	Akiyama			
	VS	5,057,694	10/15/91	Idaka et al.			
	VT	5,635,453	06/03/97	Pique et al.			
	VU	5,719,417	02/17/98	Roeder et al.			
	W	5,998,819	12/07/99	Yokoyama et al.			
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	w	2002/0079576	06/27/02	Seshan					
	vx	5,148,504	09/15/92	Levi et al. /					
	VY	2002/0195610 A1	12/26/02	Klosowiak					
	VZ	5,477,363	12/19/95	Matsuda					
	WA	5,905,571	05/18/99	Butter et al.			<del></del>		
	WB	5,570,226	10/29/96	Ota					
	wc	5,087,829	02/11/92	Ishibashi et al.					
	WD	2001/0020278 A1	09/06/01	Saito					
	WE	6,496,469 B1	12/17/02	Uchizaki					
	WF	5,679,947	10/21/97	Doi et al.					
	WG	2001/0036142 A1	11/01/01	Kadowaki et al.					
	WH	5,446,719	08/29/95	Yoshida et al.					
	WI	5,831,960	11/03/98	Jiang et al.		Ì			
	WJ	5,693,140	12/02/97	McKee et al.					
	WK	6,376,337 B1	04/23/02	Wang et al.			•		
	WL	4,177,094	12/04/79	Kroon					
	WM	5,216,359	06/01/93	Makki et al.					
	WN	6,307,996 B1	10/23/01	Nashimoto et al.					
	wo	5,371,621	12/06/94	Stevens					
	WP	2002/0145168 A1	10/10/02	Bojarczuk, Jr et al.					
	WQ	3,617,951	11/02/71	Anderson					
	WR	5,838,053	11/17/98	Bevan et al.					
	ws	5,684,302	11/04/97	Wersing et al.					
	WT	5,959,308	09/28/99	Shichijo et al.					
	WU	5,362,972	11/08/94	Yazawa et al.					
	wv	5,864,171	01/26/99	Yamamoto et al.					
	ww	5,028,563	07/02/91	Feit et al.					
	wx	5,937,115	08/10/99	Domash					
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	WY	5,878,175	03/02/99	Sonoda et al.	l				
	WZ	4,801,184	01/31/89	Revelli		•			
	XA	5,140,387	08/18/92	Okazaki et al.					
	ХВ	5,410,622	04/25/95	Okada et al.					
	XC	6,064,783	05/16/00	Congdon et al.					
	XD	5,772,758	06/30/98	Collins et al.					
	ΧE	5,666,376	09/09/97	Cheng			•		
	XF	5,976,953	11/02/99	Zavracky et al.					
	XG	5,578,162	11/26/96	D'Asaro et al.					
	XH	5,585,167	12/17/96	Satoh et al.					
	XI	5,674,813	10/07/97	Nakamura et al.					
	ΧJ	5,574,296	11/12/96	Park et al.					
	ХК	6,504,189	01/07/03	Matsuda et al.					
	XL	5,987,196	11/16/99	Noble					
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	XN	6,233,435 B1	05/15/01	WONG					
-	хо	4,723,321	02/02/88	SALEH					
	XP	6,181,920 B1	01/30/01	DENT ET AL					
	XQ	6,415,140 B1	07/02/02	BENJAMIN ET AL					
	XR	5,760,740	06/02/98	BLODGETT					
	xs	5,238,877	08/24/93	RUSSELL					
	хт	4,876,218	10/24/89	PESSA ET AL					
_	ΧU	6,232,242 B1	05/15/01	HATA ET AL					
	XV.	4,378,259	03/29/83	HASEGAWA ET AL					
	xw	6,278,541 B1	08/21/01	BAKER					
	XY	4,298,247	11/03/81	MICHELET ET AL					
	XZ	4,174,504	11/13/79	CHENAUSKY ET AL					
	YA	3,758,199	09/11/73	THAXTER					
	YB	6,362,558 B1	03/26/02	FUKUI					
	YC	6,140,746	10/31/00	MIYASHITA ET AL					
	YD	2002/0076878 A1	06/20/02	WASA ET AL					
	YE	6,419,849 B1	07/16/02	QIU ET AL					
	YF	2002/0179000 A1	12/05/02	LEE ET AL					
	YG	6,341,851	01/29/02	TAKAYAMA ET AL					
	ΥH	2001/0055820 A1	12/27/01	SAKURAI ET AL					
	ΥI	6,204,525 B1	03/20/01	SAKURAI ET AL					
	YJ	5,985,404	11/16/99	YANO ET AL					
	ΥK	6,538,359 B1	03/25/03	HIRAKU ET AL					
	YL	6,498,358 B1	12/24/02	LACH ET AL					
	YM	5,387,811	02/07/95	SAIGOH					
	YZ	5,523,602	06/04/96	HORIUCHI ET AL					
	YO	5,362,998	11/08/94	IWAMURA ET AL					
	YP	5,188,976	02/23/93	KUME ET AL					
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	YV	6,291,866	09/18/01	WALLACE				
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	YX	5,548,141	08/20/96	MORRIS ET AL				
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	YZ	6,110,840	08/29/00	YU				
	ZA	5,667,586	09/16/97	EK ET AL				
	ZB	5,313,058	05/17/94	FRIEDERICH ET AL				
	ZC	5,315,128	05/24/94	HUNT ET AL				
	ZD	5,919,522	07/06/99	BAUM ET AL				
	ZE	4,843,609	06/27/89	OHYA ET AL				
	ZF	4,626,878	12/02/86	KUWANO ET AL				
	ZG	4,525,871	06/25/85	FOYT ET AL				
	ZH	3,818,451	06/18/74	COLEMAN				
	ZI	6,059,895	05/09/00	CHU ET AL				
	ZJ	4,447,116	05/08/84	KING ET AL				
	ZK	6,022,671	02/08/00	BINKLEY ET AL				
	ZL	5,754,714	05/19/98	SUZUKI ET AL				
	ZM	6,524,651 B2	02/25/03	GAN ET AL				
	ZN	6,355,945 B1	03/12/03	KADOTA ET AL				
	ZO	5,642,371	06/24/97	TOHYAMA ET AL				
	ZP	6,445,724 B2	09/03/02	ABELES			<u></u> .	
	ZQ	5,753,934	05/19/98	YANO ET AL				
	ZR	6,326,667 B1	12/04/01	SUGIYAMA ET AL				
	zs	6,051,874	04/18/00	MASUDA				
	ZT	5,166,761	11/24/92	OLSON ET AL				
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	CCA	5-238894	09/17/93	JAPAN W/ENGLISH ABSTRACT				
	ССВ	2 152 315	07/31/85	GREAT BRITAIN				
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	CCD	2000-278085	10/06/00	JAPAN (ENGLISH ABSTRACT)				
	CCE	WO 03/012874	02/13/03	WIPO				
	CCF	1 043 427	10/11/00	EUROPE				
	CCG	1 069 605	01/17/01	EUROPE				
	ССН	WO 02/099885	12/12/02	WIPO				
	CCI	10-269842	10/09/98	JAPAN W/ENGLISH ABSTRACT				
	CCJ	59066183	04/14/84	JAPAN (ENGLISH ABSTRACT)				
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	CCN	0 247 722	12/02/87	EUROPE				
	ссо	1 037 272	09/20/00	EUROPE				
	ССР	59-073498	04/25/84	JAPAN (ENGLISH ABSTRACT)				
	ccq	60-161635	08/23/85	JAPAN W/ENGLISH ABSTRACT				
	CCR	59-044004	03/12/84	JAPAN W/ENGLISH ABSTRACT				
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LLAC		Si Wafer"; AsiaBizTech; Nov. 2001pp. 1-	3					
LLAD		eld GaAs Breakthrough"; Micromagazine.	com (no date available); pp. 1-3					
LLAE	Jong-Gul YOON; "Growth of Ferroele Korean Physical Society (Proc. Supp	ectric LiNbO3 Thin Film on MgO-Buffered II.); Val. 29, Nov. 1996; pp. S648-S651	Si by the Sol-Gel Method*; Journal of the					
LLAF		O3 thin films by pyrosol process"; Thin S	olld Films 304 (1997); pp.239-244					
LLAG	Science and Engineering B87 (2001)	R. Droopad et al.; "Development of high dielectric constant epitaxial oxides on silicon by molecular beam epitaxy"; Materials Science and Engineering B87 (2001); pp.292-296						
LLAH	A.K. Sharma et al.; "Integration of Pb 76, No. 11; March 13, 2000; pp. 1450	A.K. Sharma et al.; "Integration of Pb(Zr0.52Ti0.48)O3 epilayers with Si by domain epitaxy"; Applied Physics Letters, Vol. 76, No. 11; March 13, 2000; pp. 1458-1460						
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LLAJ	1	duced stress tuning of electro-optic device	es"; 320 Applied Physics Letters; 59(1991) 30					
LLAK		g-Wvelength VCSELs with Various DBR Oct. 31, 1994; pp. 286-287	Materials"; University of Delaware, Materials					
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LLAN	Y. Kitano et al.; 'Thin film crystal groupp. 164-169	wth of BaZrO3 at low oxygen partial press	sure"; Journal of Crystal Growth 243 (2002);					
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	zw	6,232,806	05/15/01	WOESTE ET AL				
	ZX	5,430,397	07/04/95	ITOH ET AL				
	ZY	6,151,240	11/21/00	SUZUKI				
	ZZ	6,528,374	03/04/03	BOJARCZUK, JR ET AL				
	A1	6,589,887	07/08/03	DALTON ET AL				
	A2	5,064,781	11/12/91	CAMBOU ET AL			•	. 17
	АЗ	2002/0052061	05/02/02	FITZGERALD				
	A4	5,696,392	12/09/97	CHAR ET AL				
	A5	5,986,301	11/16/99	FUKUSHIMA ET AL				
	A6	6,329,277	12/11/01	LIU ET AL				
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	CCU	WO 02/009150	01/31/02	WIPO				
	CCV	0 766 292	04/02/97	EUROPE				
	CCW	198 29 609	01/05/00	GERMANY				
	ссх	1 069 605	01/17/01	EUROPE				
	CCY	0 828 287	03/11/98	EUROPE .				
	CCZ	1 176 230	01/30/02	EUROPE				
		OTHER RE	FERENCES (	Including Author, Title, Date, Pertinent	Pages, e	tc.)	+,	
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	LLAQ	XIAMING HU et al; "Si Proceedings, Vol. 716		mation for the epitaxial growth of SrTIO/ -266	sub 3/on s	ilicon" Mate	erials Res	earch Society
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